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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.		
09/772,986	01/31/2001	Hisao Hayashi	SON-2010	2637		
75	590 11/12/2002					
RADER, FISHMAN & GRAUER, P.L.L.C Suite 501 1233 20th Street, NW			EXAM	EXAMINER		
			TRAN, THIEN F			
Washington, DC 20036			ART UNIT	PAPER NUMBER		
			2811			

DATE MAILED: 11/12/2002

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	A ant(s)					
		09/772,986	HAYASHI ET AL.					
2	Office Action Summary	Examiner	Art Unit	_μ				
•	•	Thien F Tran	2811					
	The MAILING DATE of this communication app ars on the cover shet with the correspondence address							
Peri d for Reply								
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is-specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). - Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).								
Status	Personaive to communication(s) filed on							
1)□	Responsive to communication(s) filed on This action is FINAL. 2b) This							
2a)⊠	,		nsecution as to the	merits is				
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.								
Disposition of Claims								
, —	Claim(s) 1-12 is/are pending in the application							
4a) Of the above claim(s) $9-12$ is/are withdrawn from consideration.								
5) 🗌	Claim(s) is/are allowed.							
•	6)⊠ Claim(s) <u>1-8</u> is/are rejected.							
· · · · · · · · · · · · · · · · · · ·	Claim(s) is/are objected to.							
8) Claim(s) are subject to restriction and/or election requirement.								
Application Papers								
9) The specification is objected to by the Examiner.								
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner. Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).								
11) The proposed drawing correction filed on is: a) approved b) disapproved by the Examiner.								
If approved, corrected drawings are required in reply to this Office action.								
12) The oath or declaration is objected to by the Examiner.								
Priority under 35 U.S.C. §§ 119 and 120								
13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).								
a) ☐ All b) ☐ Some * c) ☐ None of:								
1. Certified copies of the priority documents have been received.								
	2. Certified copies of the priority documents have been received in Application No							
3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received.								
14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).								
a) The translation of the foreign language provisional application has been received.								
15) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.								
Attachment(s) 1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413) Paper No(s)								
2) Notic	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449) Paper No(s) _	5) Notice of Informal						
S Patent and T	rademark Office							

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DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-8 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hisao et al. (JP 10209467).

Hisao et al. discloses a display device (Fig. 6) comprising an insulating substrate 1; pixels 14 arranged in a matrix form; and thin film transistors 3 (Fig. 1) for driving said respective pixels, wherein said pixels and said thin film transistors are formed as integrated circuits on said insulating substrate, each of said thin film transistors has a bottom gate structure having a gate electrode 5, a gate insulating film 4 and a semiconductor thin film 2 stacked in the order from below upward, and said gate electrode is made of metallic material having a thickness of about 100 nm (about 50 nm for layer 5a and about 50 nm for layer 5b). Hisao et al. discloses said gate electrode having a thickness of about 100 nm which could be more or less of 100 nm. Therefore, the thickness of said gate electrode could be less than 100 nm that reads on the claim. Furthermore, it would have been obvious to one having ordinary skill in the art at the time the invention was made to form the gate electrode having a thickness of less than 100 nm, since it has been held that where the general conditions of a claim are disclosed in the prior art, discovering the optimum or workable ranges involves only

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routine skill in the art. In re Aller, 105 USPQ 233. In re Daily, 93 USPQ 47 (CCPA 1966), the court held that changes in size and shape of parts of an invention in the absence of an unexpected result involve routine skill in the art. Additionally, In Gardner v. TEC Systems, Inc., 725 F.2d 1338, 220 USPQ 777 (Fed. Cir. 1984), cert. denied, 469 U.S. 830, 225 USPQ 232 (1984), the Federal Circuit held that where the only difference between the prior art and the claims was a recitation of relative dimensions of the claimed device and a device having the claimed relative dimensions would not perform differently than the prior art device, the claimed device was not patentably distinct from the prior art device.

Regarding claims 2 and 6, said gate insulating film 4 has a film thickness of 150 nm which is thicker than the thickness of the gate electrode.

Regarding claims 3 and 7, said semiconductor thin film 2 comprises polycrystalline silicon crystallized by an irradiation of a laser beam.

Regarding claims 4 and 8, said gate electrode has a multi-layer structure stacked with an upper layer 5a having comparatively low heat conductivity and high electric resistance, and a lower layer 5b having comparatively high heat conductivity and low electric resistance.

Response to Arguments

Applicant's arguments filed 09-04-02 have been fully considered but they are not persuasive. Applicant argues that even though Hisao discloses gate thickness generally around 100nm, Hisao does not disclose a gate thickness that is less than 100 nm. The examiner respectfully disagrees with the remark because a gate thickness

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about 100 nm allows for thickness slightly above or less than 100 nm. Thus the range overlap. In the case where the claimed ranges "overlap or lie inside ranges disclosed by the prior art" a prima facie case of obviousness exists. In re Wertheim, 541 F.2d 257, 191 USPQ 90 (CCPA 1976); In re Woodruff, 919 F.2d 1575, 16 USPQ2d 1934 (Fed. Cir. 1990). See MPEP 2144.05.

Conclusion

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thien F Tran whose telephone number is (703) 308-4108. The examiner can normally be reached on 8:00AM - 4:30PM Monday through Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Thomas can be reached on (703) 308-2772. The fax phone numbers

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for the organization where this application or proceeding is assigned are (703) 872-9318 for regular communications and (703) 872-9319 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

tt November 6, 2002

TOM THOMAS SUPERVISORY PATENT EXAMINER TECHNOLOGY CENTER 2800